

	Application No.	Applicant(s)
Notice of Allowability	10/692,736	HAYASE ET AL.
	Examiner	Art Unit
	Toan Ton	2871
The MAILING DATE of this communication appe All claims being allowable, PROSECUTION ON THE MERITS IS herewith (or previously mailed), a Notice of Allowance (PTOL-85) NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RI of the Office or upon petition by the applicant. See 37 CFR 1.313	(OR REMAINS) CLOSED in this a or other appropriate communicati GHTS. This application is subject	application. If not included on will be mailed in due course. THIS
1. This communication is responsive to <u>07/05/05</u> .		:
2. The allowed claim(s) is/are <u>1-8</u> .		
3. The drawings filed on 27 October 2003 are accepted by the	e Examiner.	
 4. Acknowledgment is made of a claim for foreign priority un a) All b) Some* c) None of the: 1. Certified copies of the priority documents have 2. Certified copies of the priority documents have 3. Copies of the certified copies of the priority documents have International Bureau (PCT Rule 17.2(a)). * Certified copies not received: 	been received. been received in Application No.	
Applicant has THREE MONTHS FROM THE "MAILING DATE" on noted below. Failure to timely comply will result in ABANDONM THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.		ly complying with the requirements
5. A SUBSTITUTE OATH OR DECLARATION must be submit INFORMAL PATENT APPLICATION (PTO-152) which give		
6. CORRECTED DRAWINGS (as "replacement sheets") mus	t be submitted.	:
(a) Including changes required by the Notice of Draftsperson's Patent Drawing Review (PTO-948) attached		
1) ☐ hereto or 2) ☐ to Paper No./Mail Date		·
 (b) including changes required by the attached Examiner's Paper No./Mail Date 	Amendment / Comment or in the	Office action of
Identifying indicia such as the application number (see 37 CFR 1. each sheet. Replacement sheet(s) should be labeled as such in the		
7. DEPOSIT OF and/or INFORMATION about the deposit attached Examiner's comment regarding REQUIREMENT I		
Attachment(s) 1. ☑ Notice of References Cited (PTO-892) 2. ☐ Notice of Draftperson's Patent Drawing Review (PTO-948)	6. Interview Summa Paper No./Mail D	Date
 3. Information Disclosure Statements (PTO-1449 or PTO/SB/0 Paper No./Mail Date 4. Examiner's Comment Regarding Requirement for Deposit of Biological Material 	8), 7. Examiner's Amen	dment/Comment ment of Reasons for Allowance
		:

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REASONS FOR ALLOWANCE

1. Claims 1-8 are allowed.

The following is an examiner's statement of reasons for allowance: the prior art of record does not anticipate nor render obvious to one ordinary skilled in the art a method of manufacturing a liquid crystal display device comprising a combination of various steps as claimed, more specifically, (c) forming a transparent electrode on the interlayer insulating film, the transparent electrode being electrically connected to the switching device through the interlayer insulating film, the step (c) including: (c1) depositing electrically conductive, transparent and amorphous material on the interlayer insulating film, (c2) patterning the material into the transparent electrode, and (c3) turning the transparent electrode into polysilicon by thermal annealing carried out after formation of an alignment film.

Kaneko ('035) discloses a method of manufacturing a liquid crystal display device comprising transparent electrode made from amorphous ITO. Peng ('075) discloses a method of patterning an ITO layer. However, neither discloses a method of manufacturing a liquid crystal display device comprising a combination of various steps as claimed, more specifically, (c) forming a transparent electrode on the interlayer insulating film, the transparent electrode being electrically connected to the switching device through the interlayer insulating film, the step (c) including: (c1) depositing electrically conductive, transparent and amorphous material on the interlayer insulating film, (c2) patterning the material into the transparent electrode, and (c3) turning the transparent electrode into polysilicon by thermal annealing carried out after formation of an alignment film.

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Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

CONCLUSION

2. The prior art made of record and not relied upon is considered pertinent to applicant's disclosure.

CONTACT INFORMATION

3. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Toan Ton whose telephone number is (571) 272-2303.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

August 20, 2005

TOANTON PRIMARY EXAMINER